

REMARKS

Claims 1 through 20 are pending in the subject application. Claims 1-4 and 7-10, 12, and 13 stand rejected under 35 U.S.C. 103(a). Claims 5, 6, 11, and 14-20 have been allowed. Claims 1-3, 7-9, and 11-13 have been amended.

The Applicant appreciates the Examiner's thorough examination of the subject application and respectfully requests reconsideration of the subject application based on the above amendments and the following remarks.

35 U.S.C. § 103(a) REJECTIONS

The Examiner has rejected claims 1-4, 8-10, and 13 under 35 USC 103(a) as being unpatentable over the prior art in view of U.S. Patent Number 6,396,089 to Lin, et al. ("Lin" or the "Lin Reference") and claims 7 and 12 under 35 USC 103(a) as being unpatentable over the prior art in view of Lin further in view of published European patent application EP 0 887 847 A1 to DeSanti, et al. ("DeSanti" of the "DeSanti Reference"). Claims 1-3, 7-9, and 11-13 have been amended and, accordingly, the Applicant believes that the grounds for rejection are moot. Moreover, the Applicant respectfully traverses these rejections based on the above amendments and for reasons detailed below.

Claims 1-4, 8-10, and 13

The Examiner asserts that, the admitted prior art discloses all of the features of the invention as claimed except for a passivation section with a planar/flat top surface, which the Examiner maintains is taught by the Lin Reference. The Examiner further asserts that, Lin discloses a "passivation section" that includes a silicon-oxy-nitride layer 310, an oxide layer 308, an SOG layer 306, and another oxide layer 304. The Applicant respectfully maintains, however, that, Lin does not teach a thin film that is used as a passivation section. Indeed, this feature is clearly obvious in light of

allowance of claims 5, 6, and 14, which recite method steps that include "forming a thin film used for forming a passivation section."

Therefore, it is respectfully submitted that, claims 1-4, 8-10, and 13 are not made obvious by the admitted prior art in view of Lin and, further, satisfy the requirements of 35 U.S.C. 100, et seq., especially § 103(a). Accordingly, claims 1-4, 8-10, and 13 are allowable. Moreover, it is respectfully submitted that the subject application is in condition for allowance. Early and favorable action is requested.

Claims 7 and 12

Claim 7 also has been amended to recite that the claimed method includes the step of "forming a thin film used for forming a passivation section." Neither the admitted prior art nor the Lin reference teaches this feature.

Nor can the DeSanti reference make up for the deficiencies of the admitted prior art and Lin references. Specifically, DeSanti does not teach, mention or suggest a step for "forming a thin film used for forming a passivation section."

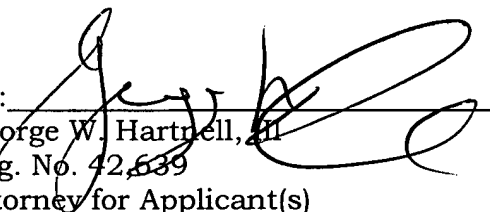
Therefore, it is respectfully submitted that, claims 7 and 12 are not made obvious by the admitted prior art in view of Lin further in view of DeSanti and, further, satisfy the requirements of 35 U.S.C. 100, et seq., especially § 103(a). Accordingly, claims 7 and 12 are allowable. Moreover, it is respectfully submitted that the subject application is in condition for allowance. Early and favorable action is requested.

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The Applicant believes that no additional fee is required for consideration of the within Response. However, if for any reason the fee paid is inadequate or credit is owed for any excess fee paid, you are hereby authorized and requested to charge Deposit Account No. **04-1105**.

Respectfully submitted,

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